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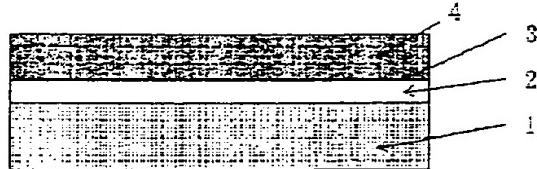
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APPLICANT : TOYO INK MFG CO LTD;

INVENTOR : KAMIMURA TOSHIKUMI;

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TITLE : FINE RESIST PATTERN FORMING
MATERIAL



ABSTRACT : PURPOSE: To obtain a cheap resist pattern forming material which enables fine patterning and gives good working environment by forming a specified plastic film as a protective film on a photosensitive layer formed on a supporting body.

CONSTITUTION: A plastic film is formed as a protective film 4 on a photosensitive layer 2 formed on a supporting body 1. This plastic film is subjected to surface treatment so that the interfacial cohesion strength between the protective layer 4 and the photosensitive layer 2 is lower than the interfacial cohesion strength between the supporting body 1 and the photosensitive layer 2 and is lower than the internal aggregation strength of the photosensitive layer 2. As for the protective layer 4, plastic films having high transparency such as polyethylene terephthalate, polyethylene naphthalate, and polyphenylene sulfite can be used. The photosensitive layer is exposed through the transparent protective film for patterning, then the protective film is peeled, and the pattern is transferred to an object for transfer by thermocompression fixing. By transferring the exposed side of the pattern forming material, higher resolution is obtd. than a conventional dry film method.

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